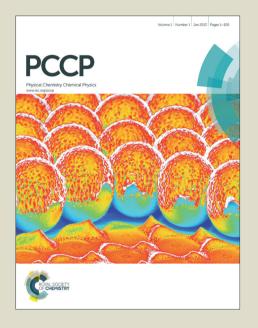


Accepted Manuscript



This is an *Accepted Manuscript*, which has been through the Royal Society of Chemistry peer review process and has been accepted for publication.

Accepted Manuscripts are published online shortly after acceptance, before technical editing, formatting and proof reading. Using this free service, authors can make their results available to the community, in citable form, before we publish the edited article. We will replace this Accepted Manuscript with the edited and formatted Advance Article as soon as it is available.

You can find more information about *Accepted Manuscripts* in the **Information for Authors**.

Please note that technical editing may introduce minor changes to the text and/or graphics, which may alter content. The journal's standard <u>Terms & Conditions</u> and the <u>Ethical guidelines</u> still apply. In no event shall the Royal Society of Chemistry be held responsible for any errors or omissions in this *Accepted Manuscript* or any consequences arising from the use of any information it contains.



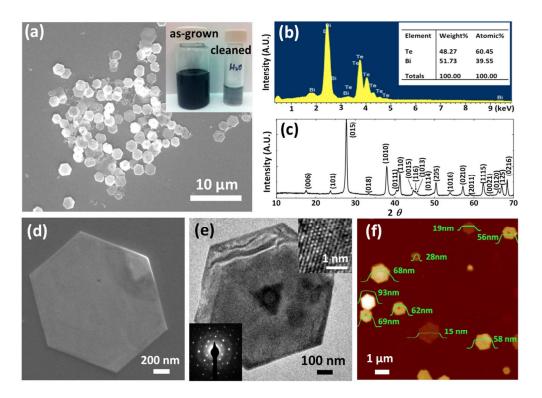


Figure 1 389x281mm (72 x 72 DPI)

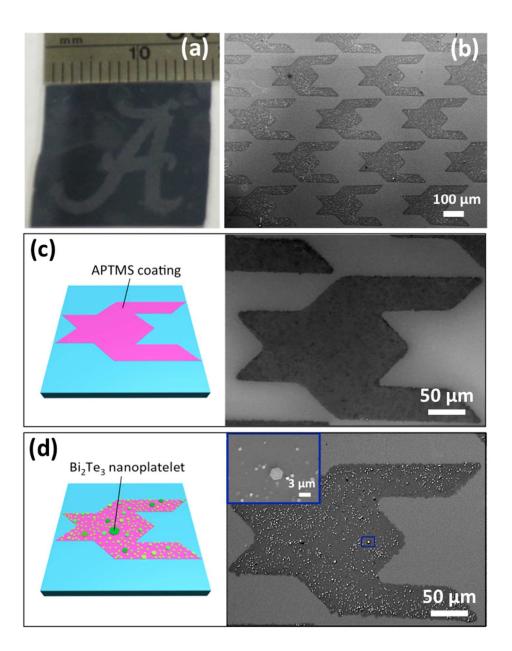


Figure 2 256x328mm (72 x 72 DPI)

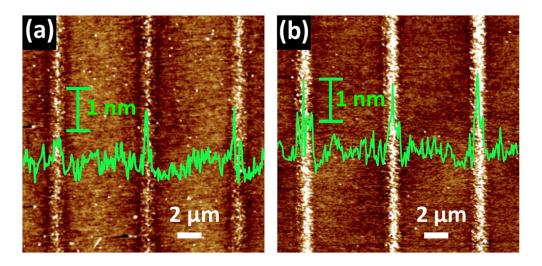


Figure 3 525x252mm (72 x 72 DPI)

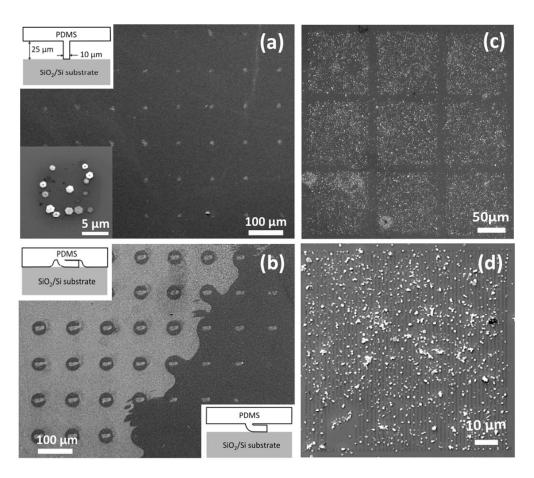


Figure 4 364x317mm (72 x 72 DPI)

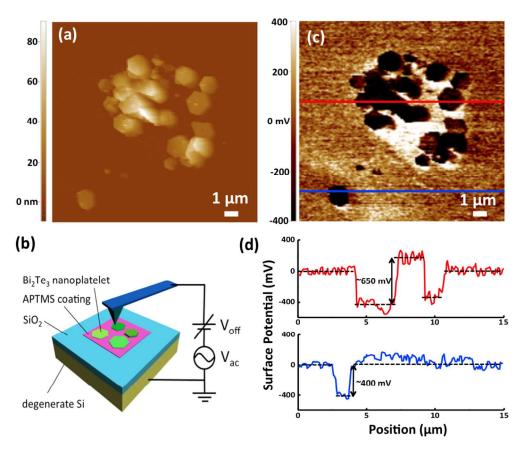


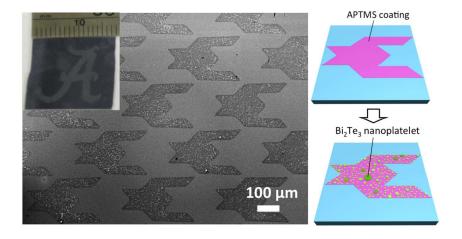
Figure 5 382x321mm (72 x 72 DPI)

Selective Adsorption of Bismuth Telluride Nanoplatelets through Electrostatic Attractions

Lingling Guo, ^{1,2} Amira Aglan, ^{1,2} Haiyu Quan, ^{1,2} Junjie Sun, ^{2,3} Chaolong Tang, ^{2,4} Jinhui Song, ^{2,4} Greg Szulczewski, ^{2,5} Hung-Ta Wang ^{1,2,a)}

a) Author to whom correspondence should be addressed. Electronic mail: <a href="https://https:

Text: A controllable adsorption of solution grown Bi₂Te₃ nanoplatelets is demonstrated.



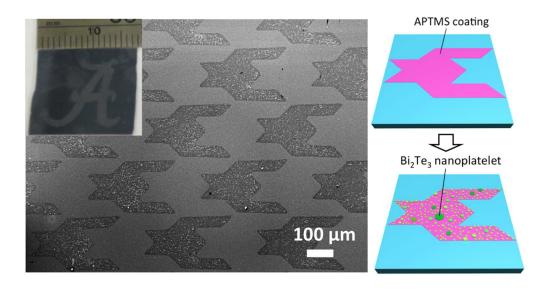
¹Department of Chemical and Biological Engineering, University of Alabama, Tuscaloosa, AL 35487, USA.

²Center for Materials of Information Technology (MINT Center), University of Alabama, Tuscaloosa, AL 35487, USA.

³School of Physics, Shandong University, Jinan, Shandong 250100, China.

⁴Department of Metallurgical and Materials Engineering, University of Alabama, Tuscaloosa, AL 35487, USA.

⁵Department of Chemistry, University of Alabama, Tuscaloosa, AL 35487, USA.



For Graphical Abstract 421x218mm (72 x 72 DPI)

Selective Adsorption of Bismuth Telluride Nanoplatelets through Electrostatic Attractions

Lingling Guo,^{1,2} Amira Aglan,^{1,2} Haiyu Quan,^{1,2} Junjie Sun,^{2,3} Chaolong Tang,^{2,4} Jinhui Song,^{2,4}

Greg Szulczewski, ^{2,5} Hung-Ta Wang ^{1,2,a)}

¹Department of Chemical and Biological Engineering, University of Alabama, Tuscaloosa, AL 35487, USA.

²Center for Materials of Information Technology (MINT Center), University of Alabama, Tuscaloosa, AL 35487,

USA.

³School of Physics, Shandong University, Jinan, Shandong 250100, China.

⁴Department of Metallurgical and Materials Engineering, University of Alabama, Tuscaloosa, AL 35487, USA.

⁵Department of Chemistry, University of Alabama, Tuscaloosa, AL 35487, USA.

a) Author to whom correspondence should be addressed. Electronic mail: httwang@eng.ua.edu

Abstract

We demonstrate a facile technique to assemble solution phase-synthesized bismuth telluride (Bi_2Te_3) nanoplatelets into arrays of micropatterns. Aminosilane self-assembled monolayers (SAMs) are printed on silicon dioxide (SiO_2) substrates using microcontact printing (μ CP). The SAM printed surfaces are terminated with amine-groups allowing Bi_2Te_3 nanoplatelet selective adsorption owing to an electrostatic attraction. Using Kelvin probe force microscopy, the electrical potential difference between aminosilane SAM and Bi_2Te_3 nanoplatelet surfaces is ~ 650 mV, which is larger than that (~ 400 mV) between SiO_2 substrate and Bi_2Te_3 nanoplatelet surfaces. The selective adsorption provides an opportunity for integrating solution phase-grown topological insulators toward several device-level applications.

Keywords: Bi₂Te₃ nanoplatelet, microcontact printing, adsorption, topological insulator.

1. Introduction

The V-VI group chalcogenides, including bismuth telluride (Bi₂Te₃), bismuth selenide (Bi₂Se₃), and antimony telluride (Sb₂Te₃), are three-dimensional topological insulators, whose surfaces are covered by the two-dimensional electron gas (2DEG) from the topological surface states. ¹⁻⁶ The novel topological surface states are induced by a strong spin-orbit coupling, and the spin carriers are protected against time reversal perturbations, e.g., surface defects and impurities, making the 2DEG spin charge transport essentially dissipation-less. ⁷ Recent advances in topological insulator research have drawn much attention due to its potential application in the next generation electronics, ^{9, 10} thermoelectrics, ¹¹⁻¹⁴ infrared detectors, ¹⁵ and heterogeneous catalysis. ¹⁶

The nontrivial topological surface states of these V-VI group chalcogenides are derived from the unique layered crystal structure. In Bi_2Te_3 , five atomic layers in the order of $Te_{(1)}$ -Bi- $Te_{(2)}$ -Bi- $Te_{(1)}$ form a charge neutral sheet with a thickness of ~1 nm, called a quintuple sheet. ^{17, 18} Stacking quintuple sheets along the *c*-axis forms the rhombohedral structure that is in the $D_{3d}^5(R\overline{3}m)$ space group. ^{19, 20} The adjacent Bi and Te atomic layers in a quintuple sheet are held by covalent forces; in contrast, the bonding between neighboring quintuple layers, i.e., between adjacent $Te_{(1)}$ atomic layers, is a weak van der Waals interaction. ^{17, 18} Because Bi_2Se_3 has a smaller van der Waals gap than Bi_2Te_3 and Sb_2Te_3 , the spin-orbit coupling in Bi_2Se_3 is stronger, and consequently the electronic structures of topological surface states in these V-VI group chalcogenides are also different. ² Topological surface states in several V-VI group chalcogenides had been revealed by angle-resolved photoemission spectroscopy, ^{1, 3, 4} scanning-tunneling microscopy, ⁷ and transport measurements. ^{5, 6} Currently, the major challenge hampering the novel 2DEG toward practical applications is that the surface spin charge transport is overwhelmed by

the ordinary bulk charges. On the other hand, there is a lack of processing techniques suitable for a large scale, device-level integration.

Previously, Bi₂Te₃ and Bi₂Se₃ nanoplatelets were synthesized on mica surfaces by a chemical vapor transport (CVT) method.²¹ On the atomically-smooth surfaces, the nanoplatelet growth could be controlled precisely along mica's crystal orientation via the van der Waals epitaxy. Later, arrays of nanoplatelets as flexible infrared transparent electrodes were also demonstrated.²² Although the van der Waals epitaxy on mica substrates is suitable for selective growth of chalcogenide-based topological insulators, mica substrates are incompatibility with common silicon manufacturing processes, which will limit its use in many applications. In contrast, solvothermal syntheses of Bi₂Te₃ nanoplatelets are facile, and nanoplatelets can be transferred to any substrate. As a result, it is important to develop methods of transferring Bi₂Te₃ nanoplatelets in well-defined positions on silicon substrate to advance the potential applications of these topological insulator nanopletelets.

In this work, we report a practical technique to assemble solution phase-grown Bi_2Te_3 nanoplatelets into micropattern arrays by the microcontact printing (μ CP) technique. ²³⁻²⁵ We demonstrate that Bi_2Te_3 nanoplatelets could selectively adsorb onto the surfaces of aminosilane self-assembled monolayers (SAMs) that were printed on silicon oxide (SiO₂) substrates using μ CP. We used Kevin probe force microscopy (KPFM) to characterize the surface electrical potentials and measured a ~650 mV potential difference between aminosilane SAMs and Bi_2Te_3 nanoplatelets. The Coulombic interaction between the protonated amine groups and Bi_2Te_3 nanoplatelets enables a robust and scalable method for selectively adsorbing solution phase-grown topological insulator nanoplatelets into micropattern arrays. Such a selective adsorption of topological insulators by aminosilane SAMs also opens the possibilities for topological insulator

surface passivation, reduction of ordinary bulk charges, and modification of topological surface states via electrostatic gating. ^{26, 27}

2. Experimental

Several solvothermal syntheses of Bi₂Te₃ nanoplatelets were previously reported using different precursors and growth conditions in a similar reducing environment. ²⁸⁻³² Our method is based the approach of Li and co-worker's. ²⁸ The Bi₂Te₃ nanoplatelets were synthesized using the general autoclave reactor (23 ml) from Parr Instrument Company. Bismuth oxide (Bi₂O₃, 99.995 %), tellurium dioxide (TeO₂, 99.995 %), ethylene glycol (EG, Reagent Grade), polyvinylpyrrolidone (PVP, average molecule weight 40,000), and sodium hydroxide flakes (NaOH, 98.7 %+) were all purchased from Alfa Aesar. All of the chemicals were used as received without further purification. In a typical synthesis, 0.1865 g of TeO₂, 0.1793 g of Bi₂O₃, 0.3044 g of PVP, and 0.3047 g of NaOH were added into 15 ml of EG. The mixture was stirred vigorously at 90 °C for 30 minutes in order to thoroughly dissolve the chemicals in EG. The precursor solution was sealed in the autoclave reactor, and the solvothermal reaction was carried out in the oven at a temperature of 210 °C for 24 hours. The as-grown nanoplatelets were collected by centrifugation, and cleaned by rinsing alternatively in de-ionized (DI) water at room temperature and 1-methyl-2-pyrrolidone (NMP) at 85 °C for five cycles. It was critical to remove PVP thoroughly to obtain clean Bi₂Te₃ nanoplatelet surfaces for the selective adsorption. The good solubility of PVP in NMP is likely due to the fact that NMP is the pendant group of the polymer, PVP. At an elevated temperature (85 °C), the solubility of PVP in NMP can be further increased. The cleaned Bi₂Te₃ nanoplatelets were characterized by scanning electron microscopy

(SEM, JEOL 7000 FE), X-ray diffraction (XRD, Bruker D8 Discover), atomic force microscopy (AFM, Park XE 70), and transmission electron microscopy (TEM, FEI Tecnai F-20).

The elastic poly(dimethylsiloxane) (PDMS) stamps for the µCP were fabricated by first mixing Sylgard 184 elastomer and curing agent (w/w=10/1) and pouring the mixture over master substrates, which were fabricated by conventional photolithography (Karl Suss MA6) with either SU8-3025 resist or Shipley 1818 resist. After baking at 70 °C for 24 hours, the PDMS was peeled off from the master and cut into a 2×2 cm stamp. To make the µCP ink, (3aminopropyl)trimethoxysilane (APTMS, 97 % from Sigma-Aldrich) was diluted in DI water to 1 % by volume, sonicated for 3 minutes, and then filtered through a syringe filter (0.2 µm pore size, from VWR). In a standard µCP process, the PDMS stamp was immersed in the filtered 1 % APTMS aqueous solution for 2 minutes and then dried by nitrogen blow. The substrate was an ntype (100) silicon substrate (phosphorus doped, resistivity= 0.001~0.005 ohm•cm) with a thermally-grown dry oxide (thickness~120 nm), which was cleaned by acetone/IPA rinses and oxygen plasma treatment before the µCP. The stamp was brought in contact with SiO₂/Si substrate for 10 to 20 s at 50 °C on the hotplate to ensure the transfer of a single molecular layer of APTMS. The APTMS printed substrate was immediately immersed in the Bi₂Te₃ nanoplatelet-dispersed aqueous solution for 2 to 20 minutes under a mild vortex action. Finally, the substrate was rinsed with DI water and blown dry by a nitrogen gun. The nanoplateletdispersed aqueous solution used for the adsorption was prepared by diluting 20 µl highlyconcentrated, cleaned nanoplatelet solution in 2 ml DI water, followed by vortex and sonication until a homogeneous nanoplatelet dispersion with a light grey color is obtained. SEM, AFM, and KPFM were used to characterize the APTMS printed and nanoplatelet-adsorbed samples.

3. Results and discussion

Figure 1 presents the structure and chemical characterization of the solution phase-grown Bi₂Te₃ nanoplatelets. As shown by SEM (**Fig. 1(a)** and **(d)**), the Bi₂Te₃ nanoplatelets have a hexagonal morphology owing to the atomic hexagonal packing in the crystal structure. Interestingly, roughly 50 % nanoplatelets have a hole in the center, which may be originated from the growth of a heterostructure of Bi₂Te₃ nanoplatelets skewered by a Te nanowire as observed in the previous reports. ^{28, 29, 32} It is likely that when Te nanowires are dissolved by NaOH, Bi₂Te₃ nanoplatelets are detached, leaving a hole in the nanoplatelet center. Quantitative analysis of the EDS spectrum (Fig. 1(b)) yields the atomic composition of Bi and Te to be 39.55 % and 60.45 %, respectively. The XRD pattern (Fig. 1(c)) of the as-synthesized Bi₂Te₃ nanoplatelets can be indexed with the rhombohedral Bi₂Te₃ crystal, and is consistent with the standard data file (PDF card no. 15-0863). In Fig. 1(e), high resolution TEM (HRTEM) and selected area electron diffraction (SAED) performed on the Bi₂Te₃ nanoplatelet show clear lattice fringes and pattern of hexagonally-symmetric spots, respectively. The AFM topographic image (Fig. 1(f)) indicates that the lateral size of the nanoplatelets is roughly in the range of 500 nm to 3 µm, and the thickness is about 10 nm to 100 nm. Collectively, the HRTEM, SAED, and XRD data indicate that our solvothermal synthesis produced highly crystallized Bi₂Te₃ nanoplatelets, which is consistent with the report of Li et al.²⁸

We note that cleaned Bi₂Te₃ nanoplatelets have a low affinity to SiO₂ surfaces using either drop casting or dip coating. A low nanoplatelet coating density was consistently obtained, and it showed trivial dependences with the nanoplatelet dispersion concentration, transferring (adsorption) time, and SiO₂ substrate hydrophobic/hydrophilic property. When a high concentration Bi₂Te₃ nanoplatelet dispersion was applied, nanoplatelets tended to aggregate to

form clusters in local regions (i.e., nanoplatelets randomly pile up), and most areas were still covered with a low density of nanoplatelets. The low affinity between the Bi_2Te_3 nanoplatelets and SiO_2 surfaces reveals a great challenge for assembling nanoplatelets toward practical applications.

To provide a feasible solution, we printed SAMs of APTMS, where were expected to have a strong affinity to Bi₂Te₃ nanoplatelet surface. Figure 2 demonstrates the selective adsorption of Bi₂Te₃ nanoplatelets using the logo of the University of Alabama. The area of the logo "A" consists of an array of APTMS printed houndstooth patterns, and Bi₂Te₃ nanoplatelets were adsorbed mainly onto the APTMS printed regions. Interestingly, nanoplatelet aggregation (or stacking) frequently observed before was greatly reduced. More importantly, and the selective adsorption can be consistently obtained, and the nanoplatelet coating density could be tuned by varying the adsorption time (shown in the Supplementary Information). This general μCP of SAMs of aminosilane was first reported for the selective adsorption of negativelycharged nanomaterials by Zhang et al.23 Despite a ~50 % self-catalyzed hydrolysis of (3aminopropyl)triethoxysilane (APTES) in aqueous solutions at room temperature, 33, 34 Zhang et al. demonstrated that using hydrophobic PDMS stamps with aqueous APTES inks could still print APTES monolayers. Although the printed APTES did not entirely form SAMs as noted in their work, the amine group terminated surfaces were very effective for the selective adsorption of citrate-coated Au nanoparticles and negatively-charged graphene oxide nanosheets. This is believed that due to an electrostatic interaction, the negatively-charged nanoparticles/nanosheets are attracted by the positively-charged, protonated amine group surfaces, resulting a controllable adsorption. 23, 35 We demonstrate that this general µCP technique is very suitable to selectively adsorb topological insulator nanoplatelets.

Although the Bi₂Te₃ nanoplatelet selective adsorption could originate from the similar electrostatic interaction, we observed that Bi₂Te₃ nanoplatelets had a distinct adsorption behavior than Au nanoparticles. 23, 35 By immersing APTMS printed substrates in Bi₂Te₃ nanoplatelet dispersed aqueous solutions, a low density of Bi₂Te₃ nanoplatelet adsorption with a poor selectivity was obtained surprisingly. In contrast, when a mild vortex was applied during the adsorption of Bi₂Te₃ nanoplatelets and while other µCP conditions were kept the same, the adsorption density was greatly increased and the adsorption selectivity was also improved. Owing to the hexagonally-shaped nanoplatelet morphology, nanoplatelet adsorption to a planar surface is limited to the top or bottom nanoplatelet surfaces. When nanoplatelets were dispersed in an unstirred aqueous solution, the nanoplatelets were observed (in an optical microscope) to undergo a flipping-type motion. Consequently, dispersed nanoplatelets had a reduced chance for the top or bottom nanoplatelet surfaces well contacting with APTMS printed surfaces to form an adsorption. This is different to Au nanoparticle adsorption, as when any points of a sphere surface in contact with a planar surface, an adsorption would easily occur. With a mild vortexing-action, the Bi₂Te₃ nanoplatelets in the dispersed aqueous solution were constantly colliding with the substrate surface, so that the chance for a face-to-face contact between nanoplatelet top/bottom surfaces and APTMS surfaces was highly increased. At the same time, when nanoplatelets were in contact with bare SiO₂ surfaces, the low affinity might not be strong enough to retain the adsorption, and nanoplatelets could be carried away by the vortex.

In order to obtain a stronger electrostatic interaction for Bi_2Te_3 nanoplatelet adsorption, we used *in situ* annealing during the μ CP at a temperature of 50 °C. As shown in **Figure 3**, the thickness of the APTMS coating clearly increased from 4 - 20 Å (μ CP at room temperature) to 8 - 20 Å (μ CP at 50 °C), and the density of APTMS also improved with the *in situ* annealing. It is

clear that there are still APTMS particles with a height of ~2 nm formed both with and without an *in situ* annealing, which is likely from the condensation in the aqueous ink.²³ Excluding those APTMS particles, it is shown that the average APTMS height is 4 Å without *in situ* annealing, and 8 Å with the *in situ* annealing. This implies APTMS formed sub-monolayers at room temperature, while a better packing was preferred at 50 °C to produce a monolayer.³³ It was previously reported that in toluene (i.e., no hydrolysis effect), *in situ* annealing at 70 °C could improve the packing quality of APTES on SiO₂ surfaces.³⁶ This is explained by the fact that the *in situ* annealing facilitates the formation of horizontal Si-O-Si bonds between adjacent APTES molecules, and the effect is an increased packing density. We suspect that the *in situ* annealing during μCP also improved the APTMS packing quality via the similar mechanism (i.e., formation of horizontal Si-O-Si bonds between APTMS). As the amine group density was increased from a closely packed APTMS SAM, Bi₂Te₃ nanoplatelet adsorption selectivity was repeatedly obtained.

We further present the selective adsorption of Bi_2Te_3 nanoplatelets using stamps of either $10\times10~\mu m$ square array (as shown in Fig. 4(a) and (b)) or $1\times100~\mu m$ line array (as shown in Fig. 4(c) and (d)). Due to the softness of the PDMS and the dimension of the square pillar array (shown in Fig. 4(a) inset), the PDMS stamps could sag and/or collapse to cause different μCP patterns. As shown in Fig. 4(a) and (b), the selective adsorption of Bi_2Te_3 nanoplatelets reveals the three μCP patterns, induced by the PDMS stamp (1) contacted normally, (2) collapsed plus sagged, and (3) collapsed only, respectively. This result shows that the selective adsorption could be robustly obtained on a $10\times10~\mu m$ APTMS printed surface. To further test the robustness of the selective adsorption, we used PDMS stamps with the $1\times100~\mu m$ line array. Fig. 4(c) and (d) show that Bi_2Te_3 nanoplatelets mainly adsorb onto the APTMS printed lines. Indeed, there are

still un-wanted nanoplatelets adsorbed on the bare SiO₂ surface due to the affinity between Bi₂Te₃ nanoplatelets and SiO₂ surfaces. Nevertheless, it should be noted that the line width is comparable with the nanoplatelet lateral size, suggesting that under a vortex motion, the electrostatic interaction between Bi₂Te₃ nanoplatelets and APTMS printed surfaces is quite reliable to produce the nanoplatelet selective adsorption.

To understand the electrostatic interaction between APTMS monolayer and the Bi₂Te₃ nanoplatelet surfaces, we examined the adsorbed Bi₂Te₃ nanoplatelets by KPFM. As shown in **Figure 5**, the surface electrical potential difference between Bi₂Te₃ surfaces and APTMS printed surfaces is about 650 mV. In comparison, the surface electrical potential difference between Bi₂Te₃ surfaces and SiO₂ surfaces is ~400 mV, which is comparable to the report of Hao *et al.*³⁷ It should be noted that the surface electrical potentials are measured under ambient conditions and not in an aqueous environment. With the existence of electrical double layers formed on the charged surfaces in an aqueous solution,³⁸ the electrostatic forces experienced by the Bi₂Te₃ nanoplatelets during the adsorption should be quite different from what was measured by KPFM. Nevertheless, our data has implied that in an aqueous solution, the electrostatic attraction force between APTMS surfaces and Bi₂Te₃ nanoplatelets was stronger than that between bare SiO₂ surfaces and Bi₂Te₃ nanoplatelets, allowing the selective adsorption of Bi₂Te₃ nanoplatelets.

4. Conclusion

In summary, we have presented a practical method to selectively adsorb solution phase grown topological insulator nanoplatelets onto APTMS printed surfaces via μ CP. Owing to the specific nanoplatelet morphology, a vortex treatment during the adsorption facilitates the nanoplatelet adsorption and simultaneously improves the adsorption selectivity. We also show

that APTMS monolayer packing can be improved by an *in situ* annealing at 50 °C during μCP, which further enhances the nanoplatelet adsorption. The electrical potential difference, measured by KPFM, between aminosilane SAMs and Bi₂Te₃ nanoplatelet surfaces is larger than that between SiO₂ and Bi₂Te₃ surfaces. We attribute the selective adsorption of Bi₂Te₃ nanoplatelets to this electrostatic interaction. Such a general adsorption of negatively-charged topological insulators is suitable for a large-scale assembly and device level fabrication.

Acknowledgements

This work at the University of Alabama (UA) is supported by the UA start-up fund and the 2012 UA Research Grants Committee (RGC) award. L. Guo would like to acknowledge the support from UA MINT Graduate Student Scholarship. A. Aglan would like to acknowledge the support from the National Science Foundation Research Experiences for Undergraduates Program (EEC-1005191; National Academy Grand Challenges), and the UA Emerging Scholar program. J. Sun would like to acknowledge the 2013 Summer Internship Program (SIP) hosted by the UA MINT Center. Authors greatly acknowledge the instrumental supports from UA Microfabrication Facility (MFF), UA Central Analytical Facility (CAF), and the UA MINT Center.

Figure Captions

Figure 1. (a) SEM image of the cleaned Bi₂Te₃ nanoplatelets. Inset: photograph of the vials with as-grown and cleaned nanoplatelet solution. **(b)** EDS and **(c)** XRD of cleaned Bi₂Te₃ nanoplatelets. **(d)** High magnification SEM image of the Bi₂Te₃ nanoplatelet. **(e)** TEM image of the Bi₂Te₃ nanoplatelet. Insets are HRTEM and SAED, respectively. **(f)** AFM topographic image of the Bi₂Te₃ nanoplatelets with their thicknesses labeled accordingly.

Figure 2. (a) Photograph of the silicon chip with selective adsorption of Bi₂Te₃ nanoplatelets to reveal the logo of "A," in which the area consists of a houndstooth array. **(b)** SEM image of Bi₂Te₃ nanoplatelets selective adsorption onto the houndstooth array that is in a local region of the logo "A" shown in (a). **(c)** SEM image of a houndstooth pattern with APTMS coating via μCP, as illustrated by the cartoon. The dark region is the APTMS coating. **(d)** SEM image of a houndstooth pattern with the Bi₂Te₃ nanoplatelet adsorption, as illustrated by the cartoon. The white dots are nanoplatelets, as magnified in the SEM inset.

Figure 3. AFM topographic images of the APTMS coating prepared by μ CP for 10s (a) without, and (b) with 50 °C *in situ* annealing, respectively. The PDMS stamp contains an array of lines (line width × length = 1×100 μ m). The topographic profiles (the green lines) are plotted and the scale bar is 1 nm.

Figure 4. (a) SEM image of the selective adsorption of Bi_2Te_3 nanoplatelets using an array of $10\times10~\mu m$ squares. The magnified SEM image (inset) shows that the nanoplatelets adsorbed onto the APTMS printed, $10\times10~\mu m$ square. The square pattern was obtained with the stamp in a

normal contact, as illustrated in the inset. **(b)** SEM image of the selective adsorption of Bi_2Te_3 nanoplatelets reveals the two patterns printed with the stamp sagged plus collapsed (left region), and collapsed only (right region), respectively, as illustrated in the insets. Note that these two patterns and the square pattern shown in (a) were obtained from the same substrate. **(c)** SEM image of the selective adsorption using an array of $1\times100~\mu m$ lines. **(d)** Magnified SEM image shows that Bi_2Te_3 nanoplatelets adsorbed mainly onto the APTMS printed lines.

Figure 5. (a) AFM topographic image of the Bi₂Te₃ nanoplatelets adsorbed in the APTMS printed, 10×10 μm square region. **(b)** Schematic of the electrical configuration for the Kevin probe force microscope measurement. **(c)** The electrical potential image scanned in the same area as shown in (a). Note that all nanoplatelets are on the APTMS printed region, except the nanoplatelet in the left/bottom corner that is on the bare SiO₂ surface. **(d)** The surface electrical potential profiles corresponding to the red and blue line marked in (c) are plotted, respectively.

References

- Y. L. Chen, J. G. Analytis, J. H. Chu, Z. K. Liu, S. K. Mo, X. L. Qi, H. J. Zhang, D. H. Lu, X. Dai, Z. Fang, S. C. Zhang, I. R. Fisher, Z. Hussain and Z. X. Shen, *Science*, 2009, 325, 178-181.
- H. J. Zhang, C. X. Liu, X. L. Qi, X. Dai, Z. Fang and S. C. Zhang, *Nature Physics*, 2009,
 5, 438-442.
- 3. D. Hsieh, Y. Xia, D. Qian, L. Wray, J. H. Dil, F. Meier, J. Osterwalder, L. Patthey, J. G. Checkelsky, N. P. Ong, A. V. Fedorov, H. Lin, A. Bansil, D. Grauer, Y. S. Hor, R. J. Cava and M. Z. Hasan, *Nature*, 2009, **460**, 1101-1105.
- 4. Y. Xia, D. Qian, D. Hsieh, L. Wray, A. Pal, H. Lin, A. Bansil, D. Grauer, Y. S. Hor, R. J. Cava and M. Z. Hasan, *Nature Physics*, 2009, **5**, 398-402.
- 5. H. L. Peng, K. J. Lai, D. S. Kong, S. Meister, Y. L. Chen, X. L. Qi, S. C. Zhang, Z. X. Shen and Y. Cui, *Nature Materials*, 2010, **9**, 225-229.
- 6. D.-X. Qu, Y. S. Hor, J. Xiong, R. J. Cava and N. P. Ong, *Science*, 2010, **329**, 821-824.
- 7. P. Roushan, J. Seo, C. V. Parker, Y. S. Hor, D. Hsieh, D. Qian, A. Richardella, M. Z. Hasan, R. J. Cava and A. Yazdani, *Nature*, 2009, **460**, 1106-1109.
- 8. D. Kong and Y. Cui, *Nature Chemistry*, 2011, **3**, 845-849.
- 9. I. Garate and M. Franz, *Physical Review Letters*, 2010, **104**, 146802.
- 10. H. Steinberg, D. R. Gardner, Y. S. Lee and P. Jarillo-Herrero, *Nano Letters*, 2010, **10**, 5036.
- 11. A. Soni, Y. Zhao, L. Yu, K. A. Khor, M. S. Dresselhaus and Q. Xiong, *Nano Letters*, 2012.

- 12. R. J. Mehta, Y. Zhang, C. Karthik, B. Singh, R. W. Siegel, T. Borca-Tasciuc and G. Ramanath, *Nature Materials*, 2012, **11**, 233-240.
- M. T. Pettes, J. Maassen, I. Jo, M. S. Lundstrom and L. Shi, *Nano Letters*, 2013, 13, 5316-5322.
- P. Puneet, R. Podila, M. Karakaya, S. Zhu, J. He, T. M. Tritt, M. S. Dresselhaus and A.
 M. Rao, *Scientific Reports*, 2013, 3.
- 15. X. Zhang, J. Wang and S.-C. Zhang, *Physical Review B*, 2010, **82**, 245107.
- 16. H. Chen, W. Zhu, D. Xiao and Z. Zhang, *Physical Review Letters*, 2011, **107**, 056804.
- 17. D. S. Kong, W. H. Dang, J. J. Cha, H. Li, S. Meister, H. L. Peng, Z. F. Liu and Y. Cui, *Nano Letters*, 2010, **10**, 2245-2250.
- 18. D. Teweldebrhan, V. Goyal and A. A. Balandin, *Nano Letters*, 2010, **10**, 1209-1218.
- 19. Y. Feutelais, B. Legendre, N. Rodier and V. Agafonov, *Materials Research Bulletin*, 1993, **28**, 591-596.
- 20. W. Richter and C. R. Becker, *Physica Status Solidi* (b), 1977, **84**, 619-628.
- 21. H. Li, J. Cao, W. Zheng, Y. Chen, D. Wu, W. Dang, K. Wang, H. Peng and Z. Liu, *Journal of the American Chemical Society*, 2012, **134**, 6132-6135.
- H. Peng, W. Dang, J. Cao, Y. Chen, D. Wu, W. Zheng, H. Li, Z.-X. Shen and Z. Liu, *Nature Chemistry*, 2012, 4, 281-286.
- H. Li, J. Zhang, X. Zhou, G. Lu, Z. Yin, G. Li, T. Wu, F. Boey, S. S. Venkatraman and
 H. Zhang, *Langmuir*, 2009, 26, 5603-5609.
- 24. L. Libioulle, A. Bietsch, H. Schmid, B. Michel and E. Delamarche, *Langmuir*, 1998, **15**, 300-304.
- 25. D. Qin, Y. Xia and G. M. Whitesides, *Nature Protocols*, 2010, **5**, 491-502.

- 26. S. S. Hong, J. J. Cha, D. Kong and Y. Cui, *Nature Communications*, 2012, 3, 757.
- 27. D. Kim, S. Cho, N. P. Butch, P. Syers, K. Kirshenbaum, S. Adam, J. Paglione and M. S. Fuhrer, *Nature Physics*, 2012, **8**, 459-463.
- 28. G. Q. Zhang, W. Wang, X. L. Lu and X. G. Li, *Crystal Growth & Design*, 2009, **9**, 145-150.
- 29. W. Lu, Y. Ding, Y. Chen, Z. L. Wang and J. Fang, *Journal of the American Chemical Society*, 2005, **127**, 10112-10116.
- 30. W. Wang, B. Poudel, J. Yang, D. Z. Wang and Z. F. Ren, *Journal of the American Chemical Society*, 2005, **127**, 13792-13793.
- J. Zhang, Z. P. Peng, A. Soni, Y. Y. Zhao, Y. Xiong, B. Peng, J. B. Wang, M. S.
 Dresselhaus and Q. H. Xiong, *Nano Letters*, 2011, 11, 2407-2414.
- 32. H. Fang, T. Feng, H. Yang, X. Ruan and Y. Wu, *Nano Letters*, 2013, **13**, 2058-2063.
- 33. M. Zhu, M. Z. Lerum and W. Chen, *Langmuir*, 2011, **28**, 416-423.
- 34. E. T. Vandenberg, L. Bertilsson, B. Liedberg, K. Uvdal, R. Erlandsson, H. Elwing and I. Lundström, *Journal of Colloid and Interface Science*, 1991, **147**, 103-118.
- 35. J. Zheng, Z. Zhu, H. Chen and Z. Liu, *Langmuir*, 2000, **16**, 4409-4412.
- 36. R. M. Pasternack, S. Rivillon Amy and Y. J. Chabal, *Langmuir*, 2008, **24**, 12963-12971.
- 37. G. Hao, X. Qi, L. Yang, Y. Liu, J. Li, L. Ren, F. Sun and J. Zhong, *AIP Advances*, 2012,2, 012114-012118.
- J. Israelachvili, *Intermolecular and Surface Forces*, Third Edn., Academic Press, London, 2011.